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PATENT
Atty. Dkt. AMAT/4213.P1/MASK/MASK-ETCH/ARNOLD S

1765-

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

11 re Application of:
Buie, et al.

Serial No.: 10/024,958

Confirmation No.: 3439

Filed: December 18, 2001

For: Etch Process for
Photolithographic Reticle
Manufacturing With
Improved Etch Bias

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

§
§ Group Art Unit: 1765

§
§ Examiner: Kin-Chan Chen

CERTIFICATE OF MAILING
37 CFR 1.8
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The Applicants, and the Attorney who signs below on the basis of the information supplied by the inventor and the information in his file, submit herewith patents, publications, or other information of which they are aware, which may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

While the information submitted in this Supplemental Information Disclosure Statement may be material pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that any patent, publication, or other information referred to therein is prior art for this invention unless specifically designated as such.

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The patents and/or publications submitted herewith are set forth on the attached Form PTO-1449.

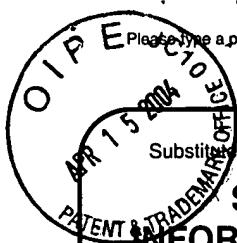
Applicants certify that all references submitted with this disclosure were first cited in a communication from a foreign patent office dated February 19, 2004, which communication is enclosed, not more than three months prior to the filing of this Supplemental Information Disclosure Statement.

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Respectfully submitted,



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**SUPPLEMENTAL
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(Use as many sheets as necessary)

Sheet 1		of 1	Application Number	10/024,958
			Filing Date	DECEMBER 18, 2001
			First Named Inventor	BUIE, ET AL.
			Group Art Unit	1765
			Examiner Name	KEN-CHAN CHEN
			Attorney Docket Number	AMAT/4213.P1/MASK/MASK-ETCH/ARNOLD S
			Submission Date	April 12, 2004

NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
	A1	PCT Search Report for PCT/US03/11549, dated February 19, 2004 (AMAT/6991.PC)	
	A2	KWON, ET AL., "Loading Effect Parameters at Dry Etcher System and Their Analysis at Mask-to-Mask Loading and Within-Mask Loading" Proceedings of SPIE, Vol. 4562 (2002) pp. 79-87.	
	A3	FUJISAWA, ET AL. "Evaluation of NLD Mask Dry Etching System" SPIE Symposium on Photomask and X-Ray Technology VI, Yokohama, JAPAN, September (1999) Vol. 3748 pp. 147-152.	
	A4	RUHL, ET AL. "Chrome Dry Etch Process Characterization Using Surface Nano Profiling" Proceedings of SPIE, Vol. 4186 (2001) pp. 97-107.	
	A5	AOYAMA, ET AL. "Advanced Cr Dry Etching Process" SPIE Symposium on Photomask and X-Ray Technology VI, Yokohama, JAPAN, September (1999) SPIE, Vol. 3748 pp. 137-146.	

Examiner	Date Considered
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